In the Specification:

Please substitute the following paragraphs for the corresponding paragraphs beginning at the indicated location in the specification as originally filed.

(page 3, lines 6+)

Another desirable feature of lithography systems is the periodic access and removal of the reticle stage for maintenance such as cleaning, replacement and the like. This is very important due to the fact that the reticle is subject to heating, high currents and other erosive factors within the vacuum chamber. These many environmental factors such as vibrations and body distortions subject the reticle stage as well as reticle table to misalignments and other accuracy considerations. However, current lithography systems provided for relatively cumbersome and complex removal of the reticle stage. These systems also do not provide and easy access to the reticle stage. By way of illustration, Figure 1 shows a highly schematic view of a conventional lithography system with a cumbersome and complex removal system. In the system shown in Figure 1, a reticle table (RT) is mounted to a reticle stage (RS) and is positionable between the projection optics (PO) and illuminator optic (IO). The conventional chamber parting line, designated as "p", is representative of a split of the vacuum chamber.

(page 3 lines 21+)

In order to remove the reticle stage in the system of Figure 1, the reticle stage must be removed in the removal direction of $Dir_0$, perpendicular to the plane of the reticle table. However, to accomplish this removal, the illuminator optics (IO) and the entire upper casing of the lithography system must be disassembled. This is mainly due to the fact that the illuminator optics, due to the design of current

systems, is supported by the upper casing of the lithography system. Then, to reinstall the reticle stage, the illuminator optics and the entire upper casing or part of the lithography system must be reassembled and realigned after the reticle stage is installed into the system. This procedure is complex and costly. It also requires a substantial amount of down time of the lithography system, which could otherwise be used for the further fabrication of semiconductor devices. Also, such a removal system requires a realignment of the reticle stage as well as the illuminator optics and other subsystems, all very costly and time consuming procedures. Additionally, there is no convenient access to the reticle stage for ~~the~~ periodic maintenance or other minor repairs or adjustments. In summary, the above difficulties present a trade-off between maintenance and throughput such that both lithographic exposure and economy are adversely affected.